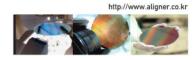
The Development and the commercialization of the Mask Aligner for wafer Midas System will continue to grow along with the value creation for our customers,





The MIDAS MDA-80MS Mask aligner is good for research and variable process of all applications. It represents next generation of full-field lithography systems.



ITEM	SPECIFICATIONS
Substrate Size	200×200mm
UV Lamp Power	1KW
Uniform Beam Size	9.25" x 9.25"
365nm Beam Intensity	20~35mW/cm ²
Beam Uniformity	≤ 4%



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